

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A substrate processing system for processing substrates, comprising:

including first to n-th processing units ($n = 1, 2, \dots, N$) unit groups, n being a positive integer, each unit group having at least one identical unit for performing processing unit and being configured to perform first to n-th wafer processing substrate processing for given periods t_1 to t_n , respectively, the processing being performed in order from the first unit to the n-th unit, a plurality of substrates being simultaneously processed by different types of the processing units for one cycle, the system comprising: ;

a loading/unloading section for taking in and out the substrates;

a first transfer section for receiving/transferring configured to receive/transfer the substrates from/to the loading/unloading section and transferring to transfer the substrates one by one to [[each]] one of the processing unit groups; and

a controller for controlling the configured to control the first transfer section and the processing units [[so]] such that each processing unit processes the substrates one by one in accordance with one cycle time as a standard time a substrate in a respective process time that is less than or equal to a standard one-cycle time, the one-cycle time being [[the]] a maximum period among periods t_1/m to t_n/m , m being a positive integer equal to the processing units actually present in each of obtained by dividing the periods t_1 to t_n by the number "m" of the identical units of the first to n-th processing units unit groups, respectively,[[;]]

wherein the processing time of each processing unit includes a pre-transfer time, a net processing time, a post-transfer time, and a waiting time, and the controller adjusts the processing time of each processing unit in accordance with the one-cycle time.

Claims 2-3 (Canceled).

Claim 4 (Currently Amended): The substrate processing system according to claim ~~[[3]]~~ 1, wherein the waiting time is ~~times are allocated before or after one of~~ added to the pre-transfer time, ~~the net processing time and~~ or the post-transfer time ~~in the processing time~~ required for each processing unit.

Claims 5-10 (Canceled).

Claim 11. (Original): The substrate processing system according to claim 1, wherein the processing units include at least one thermal processing unit.

Claim 12 (Currently Amended): The substrate processing system according to claim 11, wherein the at least one thermal processing unit ~~[[has]]~~ includes a heating mechanism and a lift-up mechanism ~~for holding~~ configured to distance each substrate ~~so that the substrate is distant~~ from the heating mechanism during the waiting time of the thermal processing unit; ~~the thermal processing unit waiting for thermal processing while the lift-up mechanism is holding the substrate as distant from the heating mechanism.~~

Claim 13 (Currently Amended): The substrate processing system according to claim 1, wherein the processing units include one developing unit ~~for developing~~ configured to develop a resist applied onto each substrate.

Claim 14 (Currently Amended): The substrate processing system according to claim 1, wherein the processing units include at least one exposing apparatus ~~for exposing~~ configured to expose a resist applied onto each substrate.

Claim 15 (Currently Amended): The substrate processing system according to claim 1, further ~~comprises~~ comprising:

a second transfer section accessible to each of the processing units ~~for transferring and~~ configured to transfer each substrate from one of the processing units to another.

Claim 16 (Currently Amended): A substrate processing system ~~including~~ for processing substrates, comprising:

first to n-th processing ~~units ($n = 1, 2, \dots, N$)~~ unit groups, n being a positive integer, each unit group having at least one ~~identical unit for performing processing unit and being~~ configured to perform first to n-th ~~wafer processing~~ wafer processing for given periods t_1 to t_n , respectively, ~~the processing being performed in order from the first unit to the n-th unit, a plurality of substrates being simultaneously processed by different type of the processing units for one cycle, the system comprising:~~ ;

a loading/unloading section ~~for taking in and out the substrates~~;

a first transfer section ~~for receiving/transferring~~ configured to receive/transfer the substrates from/to the loading/unloading section and ~~transferring to transfer~~ to transfer the substrates one by one to ~~[[each]]~~ one of the processing unit groups;

a second transfer section ~~for receiving/transferring~~ configured to receive/transfer the substrates from/to the processing units; and

a controller ~~for controlling~~ configured to control the first transfer section, the second transfer section, and the processing units, ~~when the substrates are simultaneously processed by the different types of processing units so such~~ that each processing unit processes the ~~substrates one by one~~ a substrate within a one-cycle time ~~that corresponds at least to either set as the greater of~~ a first total transfer time or a second total transfer time ~~that is larger than the other,~~

the first total transfer time being ~~the total of periods in the one cycle for~~ of a duration required for the first transfer section ~~required for receiving/transferring each substrate from/to to remove the substrate from the loading/unloading section, transfer the substrate to the one of the processing unit groups, and remove a next substrate from~~ the loading/unloading section ~~and transferring the substrate to each processing unit, and~~

the second total transfer time being ~~the total of periods in the one cycle for~~ a duration for which the second transfer section ~~required for receiving/transferring the substrate from/to the processing units~~ moves a substrate from one processing unit group to a next processing unit group.

Claim 17 (Currently Amended): The substrate processing system according to claim 16, wherein the controller calculates the maximum period among periods $t1/m$ to tn/m , m being a positive integer equal to the processing units actually present in each ~~obtained by dividing given~~ periods $t1$ to tn by the number “ m ” of the identical units of the first to n -th processing units ~~and sets the maximum among the maximum period, unit groups,~~ respectively, and

~~the first total transfer time and the second transfer time as the one-cycle time for~~
~~controlling the first and the second transfer sections~~ the controller sets the maximum period
as the first transfer time or the second transfer time.

Claim 18 (Currently Amended): The substrate processing system according to claim 16, wherein at least one of the processing units is a substrate-receiving unit ~~for receiving and processing~~ configured to receive and process each substrate, and

~~the controller calculating the total receiving and~~ calculates a processing period time
~~for the substrate-receiving unit for receiving and processing each substrate and setting the~~
~~maximum among the total receiving and processing period, and sets the processing time of~~
the substrate-receiving unit as the first total transfer time [[and]] or the second total transfer
~~time as the one-cycle time.~~

Claim 19 (Currently Amended): The substrate processing system according to claim 16, further comprising:

an exposing apparatus; and

a third transfer section ~~for receiving~~ configured to receive the substrates from the
processing units and ~~transferring~~ transfer the substrates to the exposing apparatus,

wherein the controller sets the maximum among the first total transfer time, the
second total transfer time, and a third total transfer time ~~[[for]]~~ of the third transfer section
~~required for the one-cycle,~~ as the one-cycle time.

Claim 20 (Currently Amended): A method of processing substrates with first to n-th
processing units ~~($n = 1, 2, \dots, N$)~~ unit groups, n being a positive integer, each unit group
having at least one ~~identical unit for performing~~ processing unit and being configured to

perform first to n-th wafer processing substrate processing for given periods t_1 to t_n ,
respectively, ~~the processing being performed in order from the first unit to the n-th unit, a~~
~~plurality of substrates being simultaneously processed by different types of the processing~~
~~units for one cycle~~, the method ~~comprises the steps of~~ comprising:

processing the substrates in each processing unit, one by one, for a respective
processing time that is less than or equal to a standard ~~in accordance with~~ one-cycle time as a
~~standard time~~, the one-cycle time being ~~[[the]]~~ a maximum period among periods t_1/m to
 t_n/m , m being a positive integer equal to ~~obtained by dividing the periods t_1 to t_n by the~~
~~number “m” of the identical units of the processing units actually present in each of the first~~
~~to n-th processing units~~ unit groups, respectively,[[; and]]

~~performing processing to each substrate in at least one of the processing units with~~
~~unit having a waiting time;~~

wherein the processing time of each processing unit includes a pre-transfer time, a net
processing time, a post-transfer time, and a waiting time, and the controller adjusts the
processing time of each processing unit in accordance with the one-cycle time.